Safety
- Orange UV glasses are recommended during exposure, but not required
- No buddy system restrictions imposed on normal operation

Process Restrictions

Material Restrictions
- 4" - 9" masks, up to 200mm wafers, up to 0.25" thick
- Back of substrate must be CLEAN - NO RESIST on back

Parameter Restrictions
- Use g-line or i-line resists with 405nm mirror set
- 8" maximum exposure area
- 50mm minimum microscope separation

Scheduling / Sign-up Restrictions – Minimum Tool Time: 15 minutes
- Maximum 4 hour block reservations anytime - Maximum 12 hours reserved in advance - No consecutive research group reservations - Users/Groups may use any amount of unreserved time - Additional individual restrictions may be imposed to maximize use

Requirements (Do Every Time)
- Change hardware, PUT AWAY unused parts
- Clean up - NO items on countertop - Check vacuum gaskets

Prohibitions (Never Do)
- NEVER Adjust Power Supply
- NEVER Operate when alarm sounds
- NEVER Operate without proper eye protection

Common Problems

<table>
<thead>
<tr>
<th>Problem:</th>
<th>Root Cause:</th>
<th>Solution:</th>
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</thead>
<tbody>
<tr>
<td>- Vacuum low</td>
<td>- Gasket off support</td>
<td>- Reposition gasket</td>
</tr>
<tr>
<td>- Alignment microscope out of focus</td>
<td>- Mask upside down</td>
<td>- Reload mask correctly</td>
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</tbody>
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Other Comments or Cautions
- Make sure mask and wafer are CLEAN
- Edge bead should be removed when using thick resist (>3um)
- Remember to use planarization button